

EUV Source Workshop

**Hilton Hotel, Santa Clara
Sierra Ballroom
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Meeting Highlights

- **120 attendees from 57 Organizations**
- **Stepper Manufacturer requirements have increased:**
 - EUV power (in band) is 115 W , previous requirements were 80W-120 W
 - Repetition frequency requirements are 10-7 K Hz (not unanimous), previous requirements were >6K Hz
- **Some specifications not agreed among stepper suppliers or TBD:**
 - Etendue of source output and maximum solid angle input to illuminator
 - Spectral Purity requirements
- **A typical throughput model, explaining source power requirements is presented by stepper suppliers**

Meeting Highlights

- **Source power output for continuous operation in-band in 2π continues to increase (in the last 4 months)**

- **LPP**

	October 02	Feb 03
• Supplier A	12 W	22 W 5 KHz

- **Gas Discharge**

• Supplier B	27 W	50 W 1 KHz
• Supplier C	60 W	60 W >3KHz
• Supplier D	40 W	50 W 1KHz

- **Many suppliers have alternate materials on their roadmap to meet production requirements**
- **Industry's Consensus has been created on**
 - First version of Roadmap to address EUV Source metrology requirements
- **Generation of "First version" of agreements on**
 - EUV Source fundamental data and modeling requirements
 - Critical component life-time issues

Meeting Highlights

- **Critical issues:**
 - #1 Source Power
 - #2 Critical Component Life-time
 - #3 Global Co-operation in pre-competitive arena
 - Example : Debris mitigation for Sn sources

Announcements

- **Next EUV Source Workshop will be held on Monday, September 29th, Antwerp, Belgium, day before 2003 EUVL Symposium**
- **Thanks to Presenters, Chairpersons, Moderators, EUV Source Workshop Organization Committee, Mario Gonzales, Beth Kells and Judy Behr and Yogi Behr**